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(54) Title: POLYMERIZABLE COMPOSITION, POLYMER, RESIST, AND LITHOGRAPHY METHODS

(54) Bezeichnung: POLYMERISIERBARE ZUSAMMENSETZUNG, POLYMER, RESIST UND LITHOGRAPHIEVERFAHREN

(57) Abstract: The invention relates to a polymerizable composition for producing a resist, containing at least one unsaturated polymerizable monomer (I, II) with at least one silicon atom and at least one carbonyl group. The invention also relates to a resist produced by polymerizing these compositions and to lithography methods.

(57) Zusammenfassung: Die Erfindung betrifft eine polymerisierbare Zusammensetzung zur Herstellung eines Resists, enthaltend mindestens ein ungesättigtes, polymerisierbares Monomer (I, II) mit mindestens einem Siliziumatom und mindestens einer Carbonylgruppe. Die Erfindung betrifft auch ein Resist hergestellt durch Polymerisation der Zusammensetzungen und Lithographieverfahren.